

### **INTERVIEW SUMMARY**

On September 15, 2010, an interview with Examiner Turocy was held. Attending in person were inventor, Thomas Seidel and Brian Lu, from assignee, Aixtron, Inc. Tarek Fahmi, attorney of record, attended by phone.

During the interview, proposed amendments to claim 1, as reflected in the Interview Agenda dated September 10, 2010, were discussed. It was suggested that claim 1 be further amended to clarify that the "maximum film deposition rate" is a maximum starved ALD process film deposition rate. This recommendation has been incorporated in the above amendment to claim 1.

Distinctions between the proposed amended claim 1 and the processes discussed by Park and Matero were also discussed. These distinctions are highlighted in the Interview Agenda dated September 10, 2010, and are also discussed in detail below.

No final agreement as to patentability was reached.